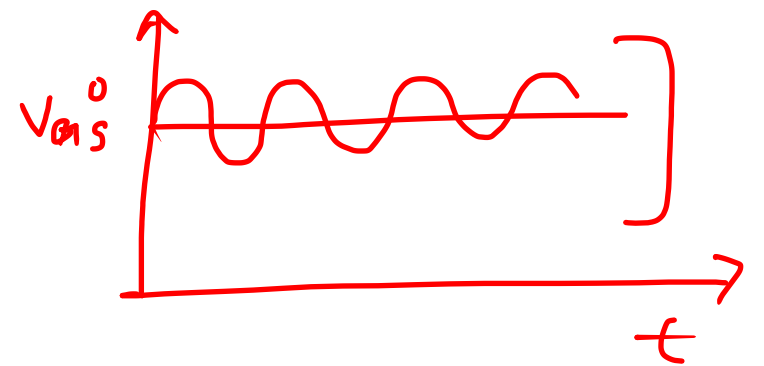
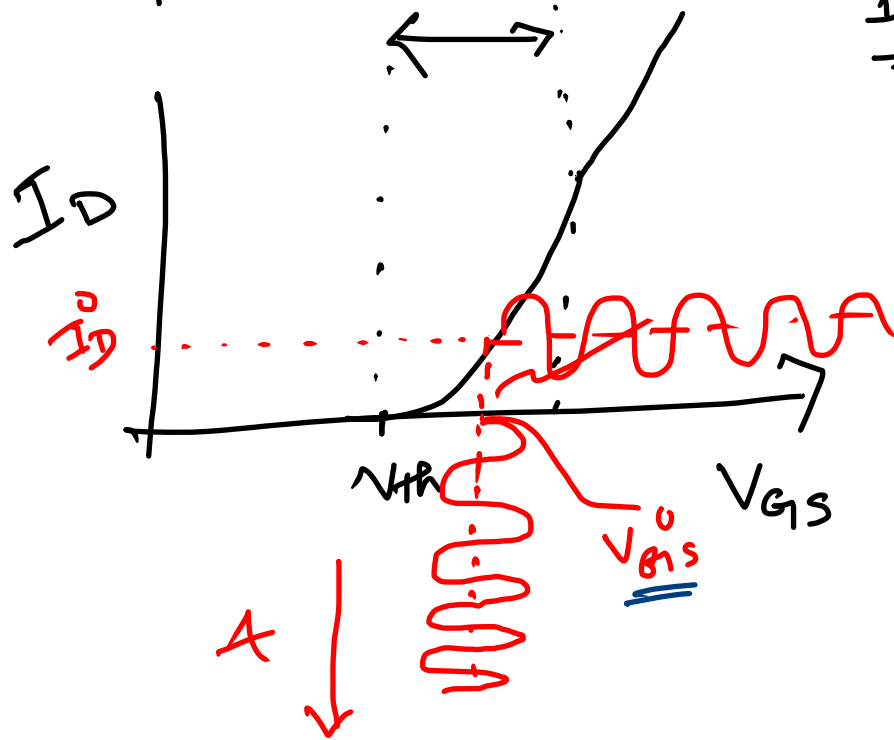
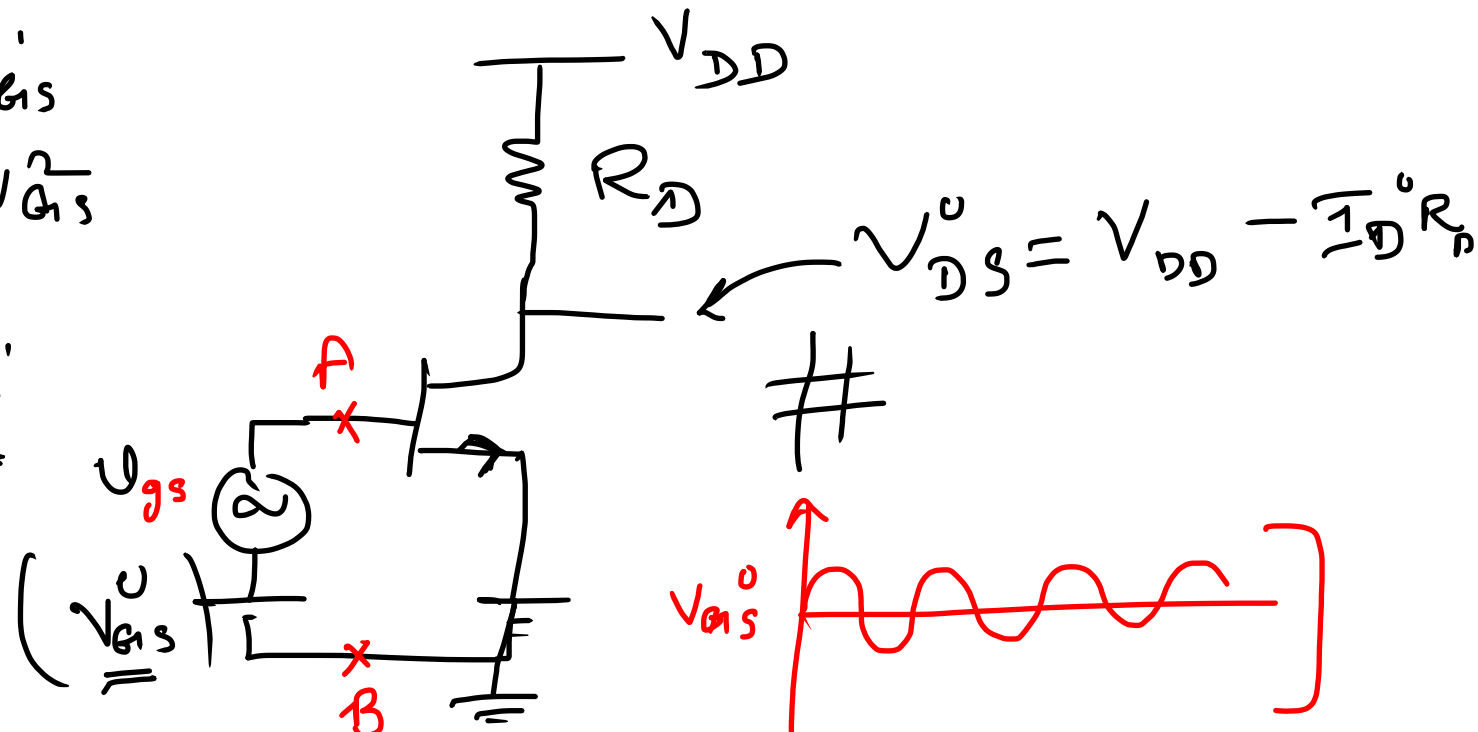
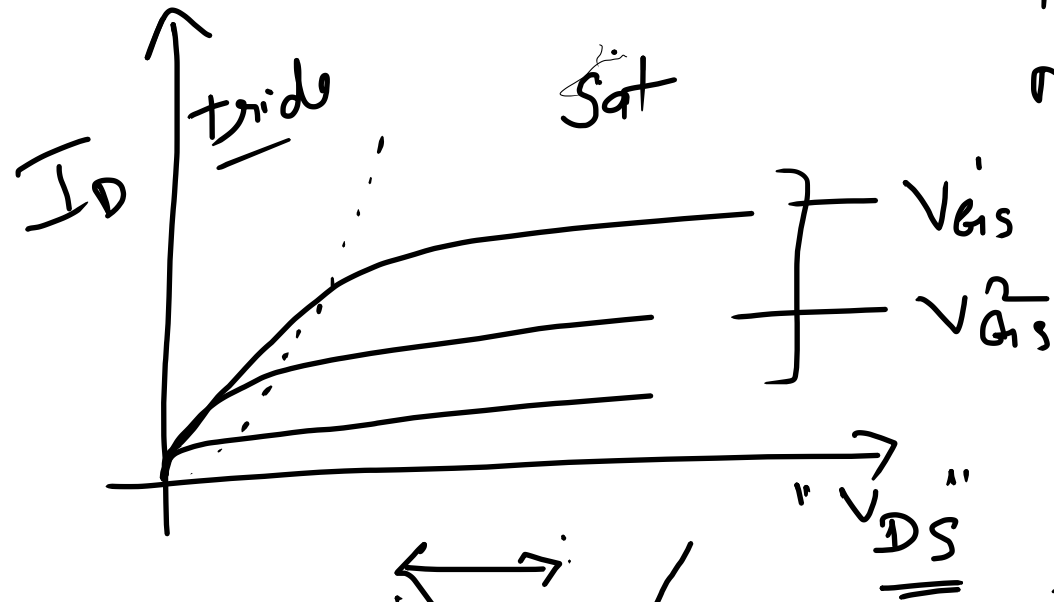
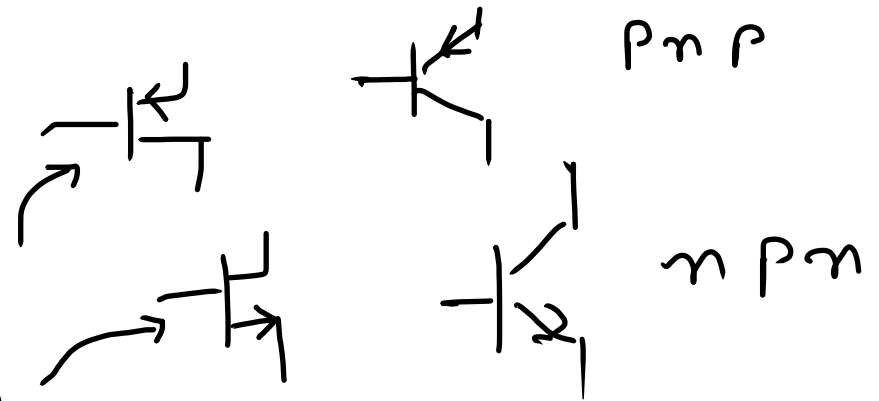


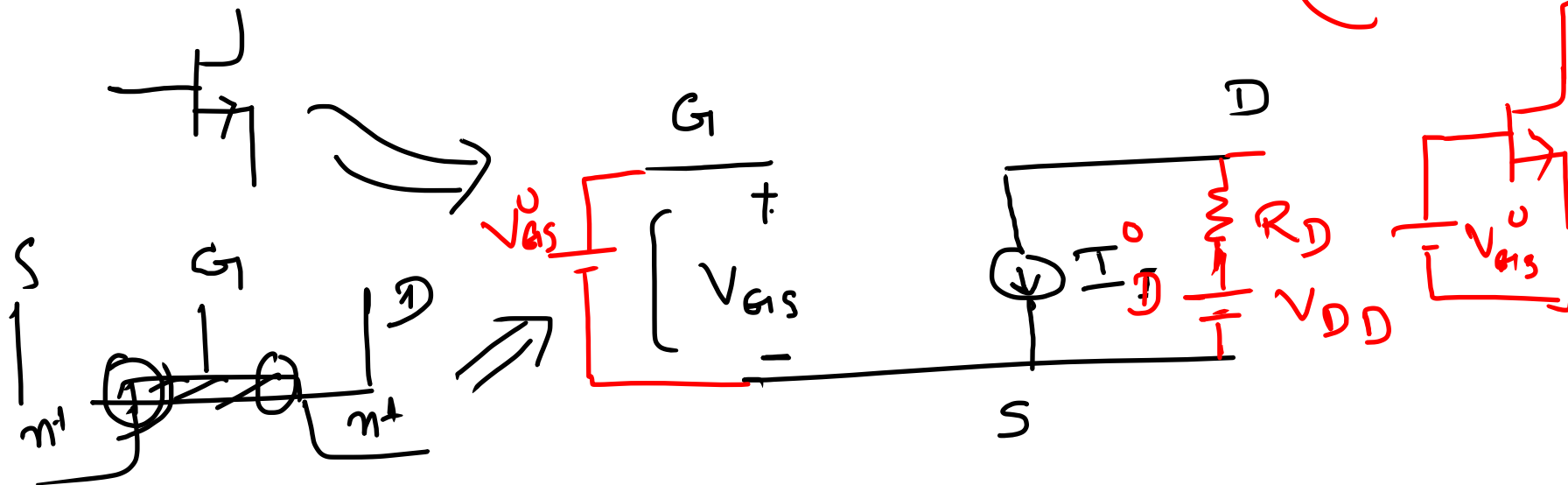
# MOSFET

P-MOS  
N-MOS



Large sig model  $\rightarrow$

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{th})^2 \quad (1)$$

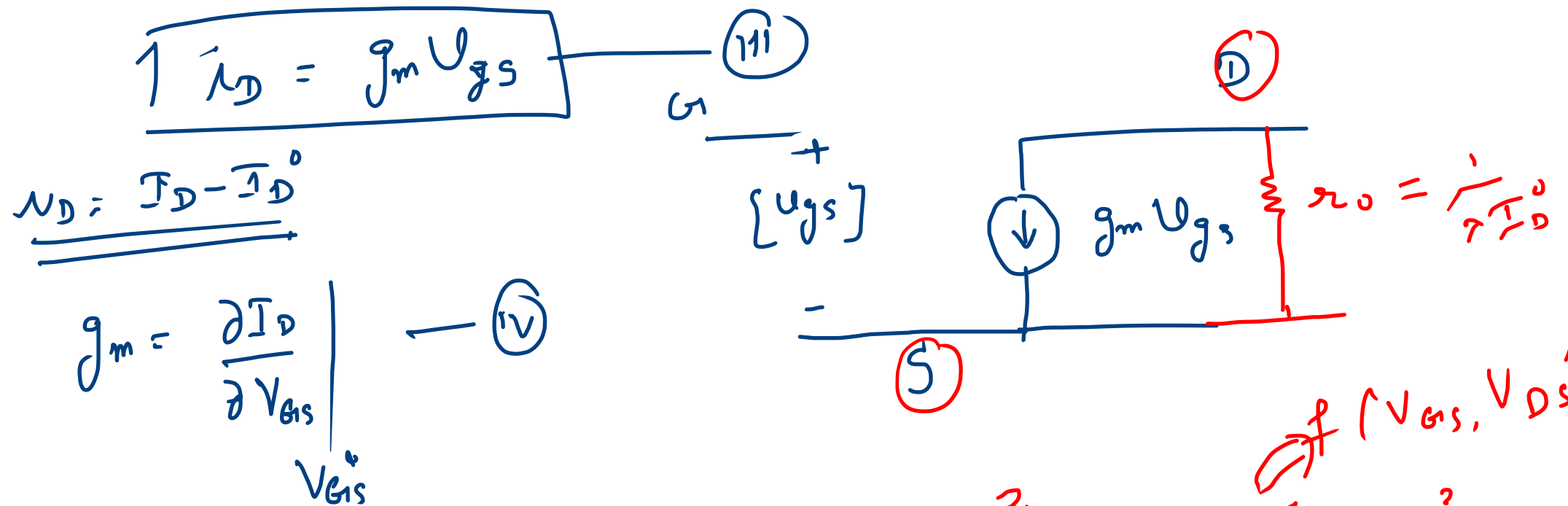


small sig model  $\rightarrow$

$$I_D = f(V_{GS}) \quad (II)$$

Linearize (II) in the neighbourhood of  $(V_{GS}^0)$

$$I_D = \underbrace{f(V_{GS}^0)}_{I_D^0} + \underbrace{\left. \frac{\partial f}{\partial V_{GS}} \right|_{V_{GS}^0}}_{g_m} \underbrace{(V_{GS} - V_{GS}^0)}_{v_{gs}} + \dots$$



$$I_D = \frac{\mu C_{ox} W}{2} \frac{(V_{gs} - V_{th})^2}{L(1 - \lambda V_{DS})} \quad (V_{gs} - V_{th})^2 \approx \frac{1}{2} \mu C_{ox} \frac{W}{L} (V_{gs} - V_{th})^2 (1 + \lambda V_{DS})$$

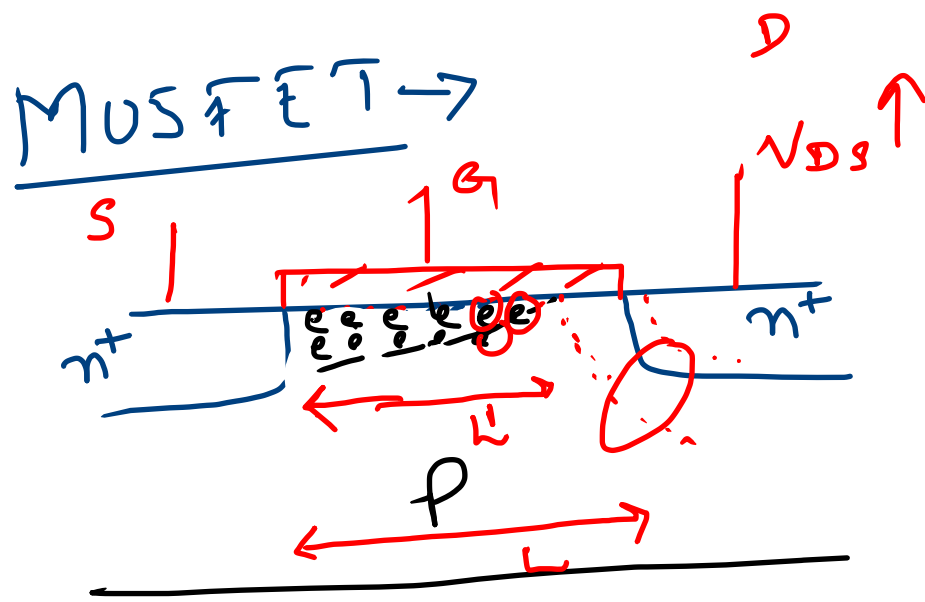
$$I_D = f(V_{gs}^0, V_{DS}^0) \rightarrow (V_{gs}^0, V_{DS}^0)$$

$$I_D = \underbrace{f(V_{gs}^0, V_{DS}^0)}_{I_D^0} + \underbrace{\frac{\partial f}{\partial V_{gs}}}_{g_m} V_{gs} + \underbrace{\frac{\partial f}{\partial V_{DS}}}_{r_o^{-1}} V_{DS}$$

$$\Rightarrow \boxed{V_D = g_m V_{gs} + r_o^{-1} V_{DS}} \quad \text{--- (v)}$$

\* p-MOS have same small sig

$$\begin{aligned}
 \frac{\partial I_D}{\partial V_{DS}} &\approx \frac{I_D^0}{r_o} \\
 \Rightarrow [r_o]^{-1} &= I_D^0
 \end{aligned}$$

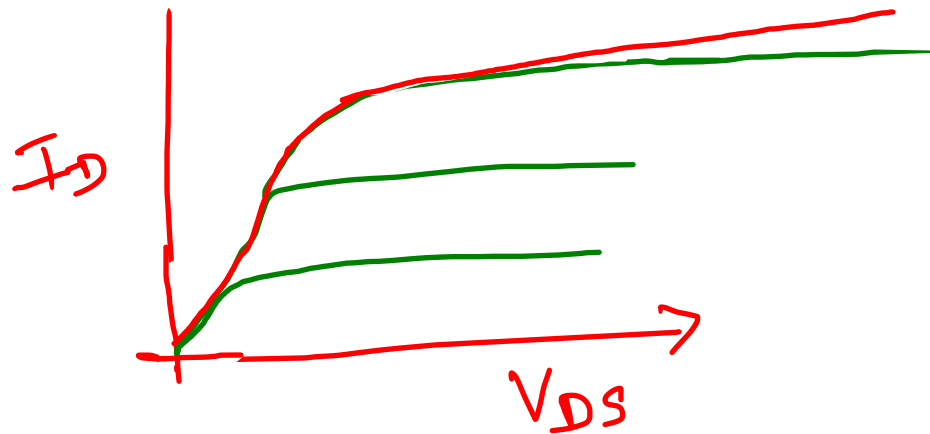
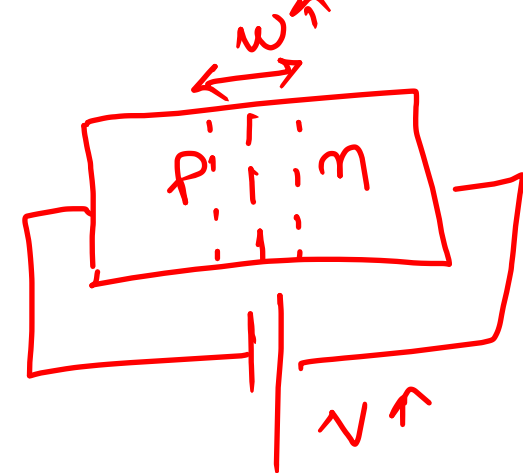


Minority carrier sweep!  
away as soon as they hit depletion region

$$V_{DS} \uparrow \quad O \propto V^n \quad \text{in } \underline{R.B}$$

$V_{DS} \uparrow$ ,  $O$  Pm depletion  $\uparrow$

$L' \downarrow$  [CLM]  
→ channel length modulation



no channel length modulation

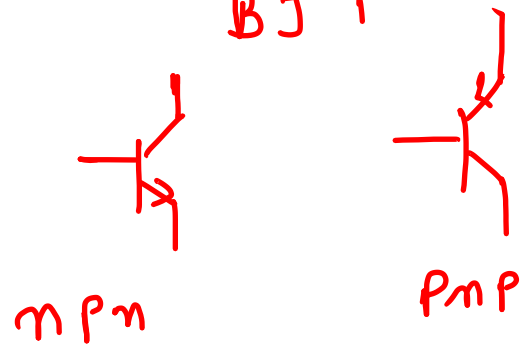
$$L' = L(1 - \gamma V_{DS})$$

CLM Factor

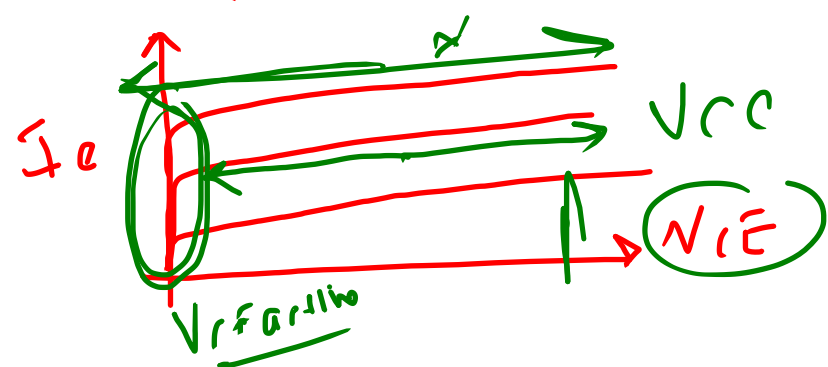
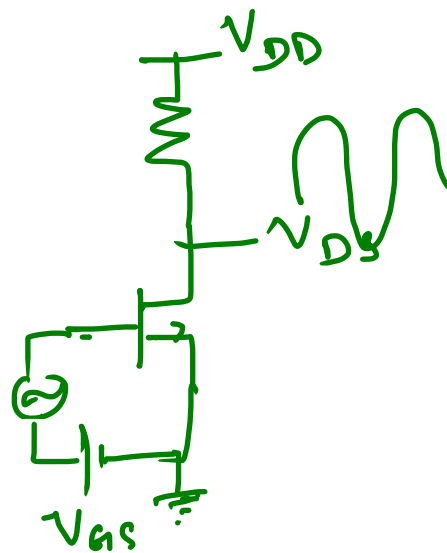
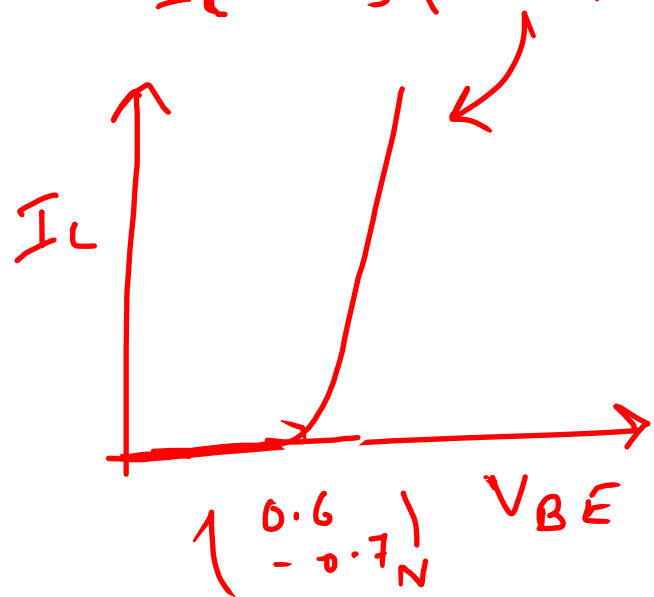
$$I_D = \frac{1}{2} \mu C_{ox} \frac{W}{L'} (V_{GS} - V_{th})^2$$

# BJT & MOSFET

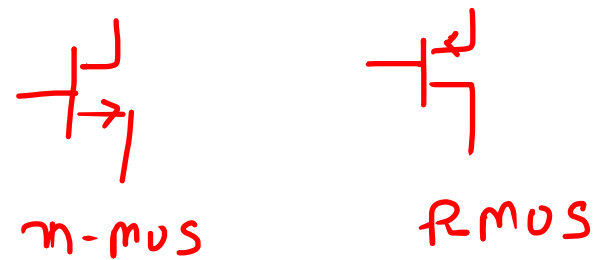
BJT



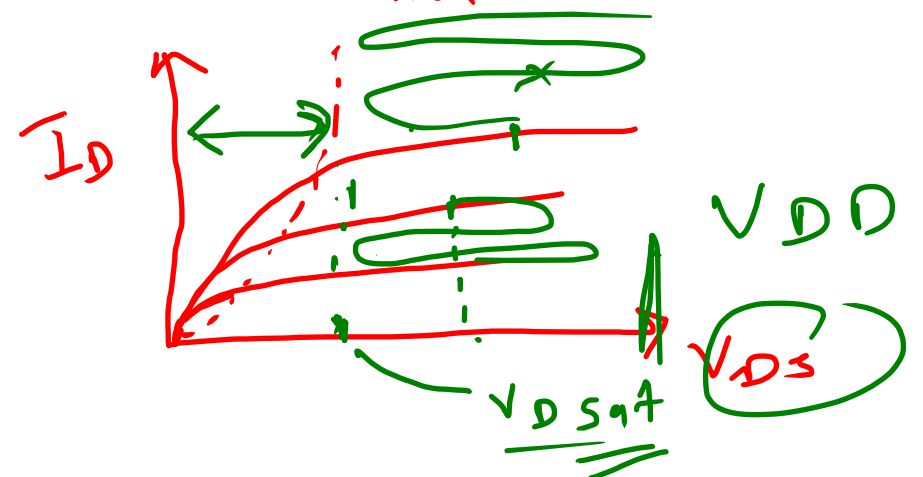
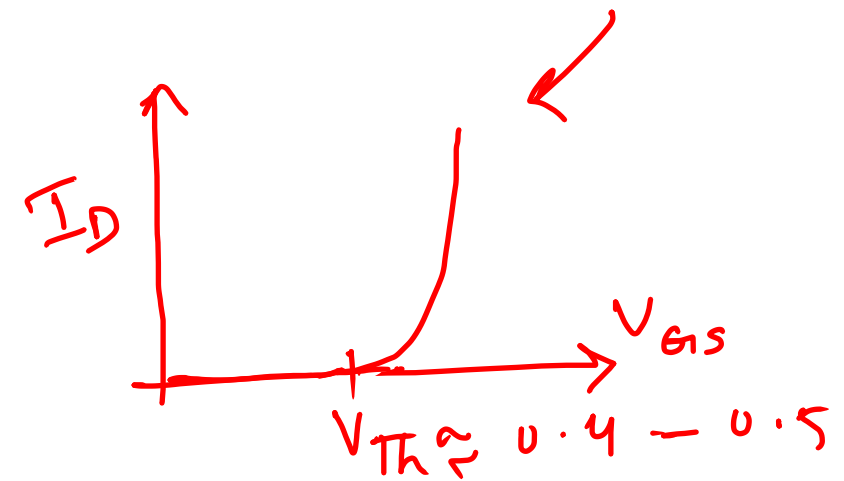
$$I_c = I_s \left( e^{\frac{V_{BE}}{V_T}} \right)$$



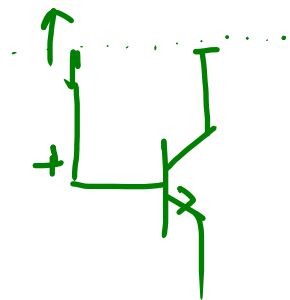
MOSFET



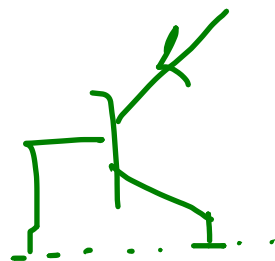
$$I_D = \frac{1}{2} \mu C_{ox} \frac{W}{L} (V_{GS} - V_{TH})^2$$



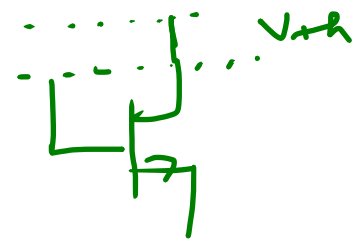
BJT



$$\underline{\underline{V_B < V_C}}$$



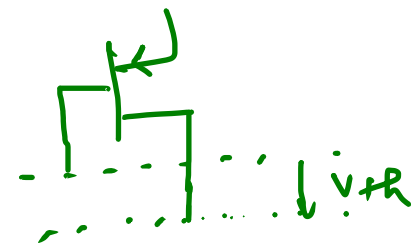
MOS



Saturation (active for amplification)

$$V_{DS} > V_{GS} - V_{TH}$$

$$V_D > V_G - V_{TH}$$

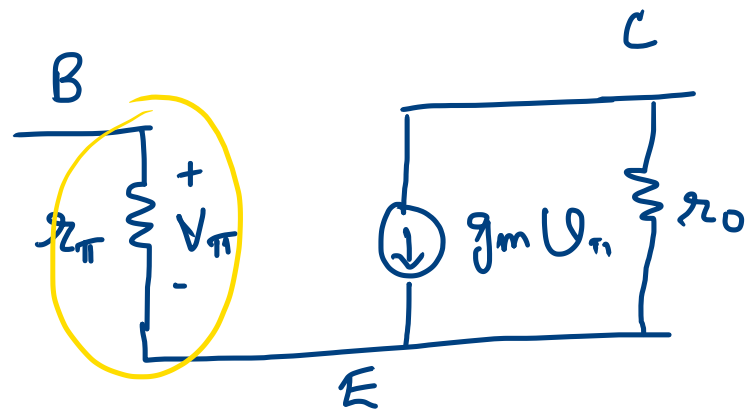


P. MOS

BJT



Large  $g_m$



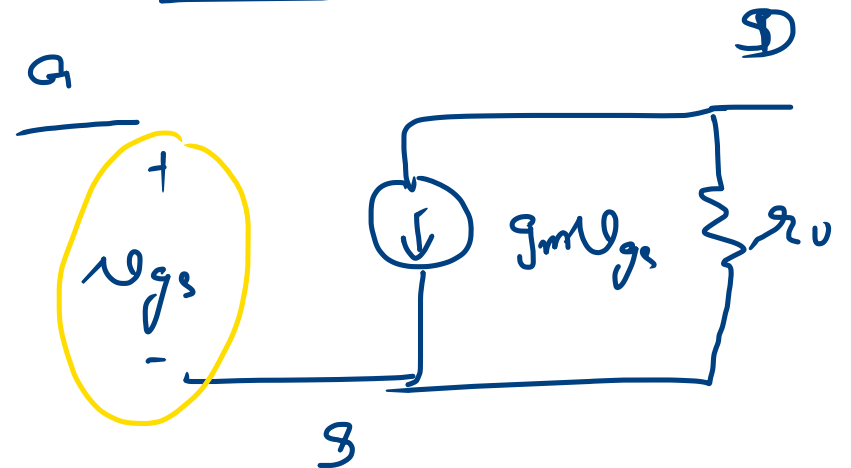
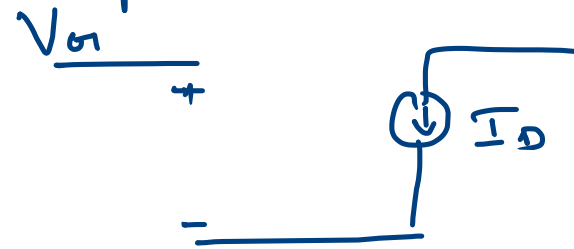
$$g_m r_{\pi} = \beta, \quad r_o = \frac{V_A}{I_C}$$

$$I_C = I_S \exp\left(\frac{V_{BE}}{V_T}\right)$$

$$g_m = \left. \frac{\partial I_C}{\partial V_{BE}} \right|_{V_{BE}} = \frac{I_C}{V_T}$$

→ offer high  $g_m$

MOSFET



$$r_o = \frac{1}{\lambda I_D}$$

$$g_m = \frac{\partial I_D}{\partial V_{GS}}$$

$$g_m = \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{th})$$

→ relative low in temp. for BJT